

IN THE SPECIFICATION:

Kindly amend the paragraph beginning at page 12, line 8 as follows.

As shown in Fig. 3c, a plurality of island shaped nano-crystalline silicon (silicon quantum dots) 44 are formed on the tunneling insulating film 43 at a size of 5nm by ~~amorphous~~ chemical vapor deposition. In particular, after seeding amorphous silicon, the insulating film 43 is formed by chemical vapor deposition method and the amorphous silicon is polished by the CMP process.